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AUG 13 2004

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Appl. No.	10/003,908	Confirmation No.	7739
First Inventor	William R. Entley	Filing Date	11/1/2001.
Tech. Center/ Art Unit	1765	Examiner	Anita Karen Alanko
Title:	In Situ Plasma Process To Remove Fluorine Residues From The Interior Surfaces Of A CVD Reactor		
Docket No.:	NVS013 US	Customer No.:	34036

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enter  
8/23/04*Santa Clara, California  
August 13, 2004MAIL STOP AF  
COMMISSIONER FOR PATENTS  
P.O. Box 1450  
Alexandria, VA 22313-1450AMENDMENT AFTER FINAL ACTION

Dear Sir:

In response to Office Action dated May 19, 2004, please amend the above-identified application as follows.

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 6 of this paper.